

REMARKS

Entry of the foregoing, reexamination and reconsideration of the subject matter identified in caption, as amended, pursuant to and consistent with 37 C.F.R. 1.112, and in light of the remarks which follow are respectfully requested.

Claims 1 and 3-8 are pending in the application.

By the foregoing amendments, claim 2 has been canceled and the features thereof have been incorporated into claim 1. In addition, claims 5-8 have been newly presented to point out further aspects of the invention.

Turning now to the Official Action, claims 1 and 4 stand rejected under 35 U.S.C. §102(b) as being anticipated by Daniels (U.S. Patent No. 5,312,715). This rejection is now moot in light of the foregoing amendment, by which the features of canceled claim 2 have been incorporated into claim 1. Accordingly, withdrawal of this rejection is respectfully requested.

Claims 1-4 stand rejected under 35 U.S.C. §103(a) as being obvious over Yezrielev (U.S. Patent No. 5,334,671) in view of Daniels. This rejection is respectfully traversed for the following reasons.

The present invention relates generally to the field of negative-type photosensitive resin compositions. In particular, this invention relates to photosensitive resin compositions containing an epoxy compound and to a method for the formation of a resist pattern using resin composition. Claim 1, as amended above, sets forth a negative-type photosensitive resin composition. The composition comprises an epoxy compound, poly(*p*-vinylphenol) and a phenol-biphenylene resin.

Based on a complete understanding of the present invention, it is respectfully submitted that the claims cannot properly be rejected based on Yezrielev in combination with Daniels.

Yezrielev relates to phenol terminated diester compositions derived from dicarboxylic acid, polyester or alkyd backbone materials, to solid crosslinked polymer compositions prepared therefrom, and to methods for improving coating properties of films and surface coatings based thereon (col. 1, lines 18-25). The non-liquid crystalline phenol-terminated diester compositions may be liquids or solids and crosslinkable

formulations containing a mixture of the phenol terminated diesters and an amino crosslinking agent (col. 3, lines 63-67). In the “Background” section, Yezrielev discloses that a number of properties are important for coating films, including hardness, flexibility, weather resistance (weatherability), chemical resistance, solvent resistance, corrosion resistance, adhesion to various substrates, and impact resistance (col. 1, lines 43-48).

Yezrielev does not disclose or suggest each feature of the presently claimed invention. For example, as correctly recognized in the Official Action, Yezrielev does not disclose or suggest poly(*p*-vinylphenol), as recited in claim 1. To cure this deficiency, the Examiner improperly relies on Daniels. In this regard, the Examiner takes the position that:

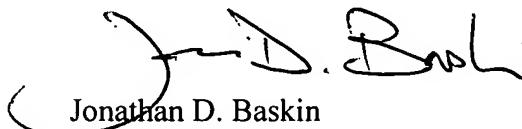
[I]t would have been obvious to one of ordinary skill in the art to prepare the material of Yezrielev et al choosing to employ the blend polymer of Daniels et al to increase the resolution of the pattern, with reasonable expectation of achieving a material having improved coating properties. (Official Action at page 6).

Applicants respectfully disagree with the Office’s position. Persons of ordinary skill in this art would not have combined the teachings of Yezrielev and Daniels in the manner suggested in the Official Action. Yezrielev discloses that the phenol terminated diester compositions may be used as a resinous component in curable coating and paint formulations. There is no suggestion in Yezrielev that the compositions disclosed therein are photoimageable or that they can or should be employed in a manner which would involve patterning, let alone patterning with increased resolution. In stark contrast to Yezrielev, Daniels relates to light-sensitive compositions and more particularly to aqueous developable light-sensitive compositions useful as high resolution soldermasks in the manufacture of printed circuit boards. There is no motivation, absent applicants’ own specification, to combine Yezrielev with Daniels in the manner suggested in the Official Action. Accordingly, withdrawal of the §103(a) rejection based on Yezrielev et al in view of Daniels et al is respectfully requested.

From the foregoing, further and favorable action in the form of a Notice of Allowance is believed to be next in order, and such action is earnestly solicited.

If there are any questions concerning this paper or the application in general, the Examiner is invited to telephone the undersigned at her earliest convenience.

Respectfully submitted,



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